

	Hits	Search Text	DBs
8	25	((organic or polymer\$4 or polyimide or polyamide or photoresist or resist) same (conductive or electroconductive or semiconduct\$4) same (dop\$4 or implant\$4 or infus\$3) same (irradiat\$4 or expos\$4 or illuminat\$4) same (UV or IR or DUV or EUV or excimer or laser or light or radiation)) and (step\$5 or (step\$4 near9 repeat) or (selectiv\$5 near12 expos\$4) or lithograph\$6 or irradiat\$4 or illuminat\$4) and (photomask or mask or reticle or pattern\$5) and ((dop\$4 or implant\$6) near22 (UV or irradiat\$4 or radiation or exops\$4)) and ((remov\$6 or etch\$6) same (weak or (less\$3 near16 (dop\$4 or implant\$4)) or unbound\$4 or non\$3bond\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
10	31	((organic or polymer\$4 or polyimide or polyamide or photoresist or resist) same (conductive or electroconductive or semiconduct\$4 or transistor) same (dop\$4 or implant\$4 or infus\$3) same (irradiat\$4 or expos\$4 or illuminat\$4) same (UV or IR or DUV or EUV or excimer or laser or light or radiation)) and (step\$5 or (step\$4 near9 repeat) or (selectiv\$5 near12 expos\$4) or lithograph\$6 or irradiat\$4 or illuminat\$4) and (photomask or mask or reticle or pattern\$5) and ((dop\$4 or implant\$6) near22 (UV or irradiat\$4 or radiation or exops\$4)) and ((remov\$6 or etch\$6) same (weak or (less\$3 near16 (dop\$4 or implant\$4)) or unbound\$4 or non\$3bond\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	1	((organic or polymer\$4 or polyimide or polyamide or photoresist or resist) same (conductive or electroconductive or semiconduct\$4 or transistor) same (dop\$4 or implant\$4 or infus\$3) same (irradiat\$4 or expos\$4 or illuminat\$4) same (UV or IR or DUV or EUV or excimer or laser or light or radiation)) and (step\$5 or (step\$4 near9 repeat) or (selectiv\$5 near12 expos\$4) or lithograph\$6 or irradiat\$4 or illuminat\$4) and (photomask or mask or reticle or pattern\$5) and ((dop\$4 or implant\$6) near22 (UV or irradiat\$4 or radiation or exops\$4)) and ((remov\$6 or etch\$6) same (weak or (less\$3 near16 (dop\$4 or implant\$4)) or unbound\$4 or non\$3bond\$4)) and (restor\$4 same conductiv\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB